



OÁYE

Oglala Lakota Arts Continuum



Residency Application

*Oglala Lakota College Artist-in-Resident
Spring 2021 Session*

Application Period: 01/29/21 - 02/26/21

*Applications will be reviewed and awarded on a first come-first serve basis.
Artists are encouraged to apply at their earliest convenience.*

Contact Information

email: oaye@olc.edu

phone: (605) 455-6093

Overview

The mission of the Oglala Lakota College OÁYE program is to support a Lakota arts continuum through artist residencies and cultural mentorships at OLC.

Description

The OÁYE - Residency is a decentralized Artist-In-Residence program at OLC, open to Master Artists and Cultural Bearers. This program offers a paid stipend, modest materials support, and opportunities to engage with OLC and Oglala Lakota communities.

Awardees will utilize their Residency to:

- continue their work and/or conduct research
- share their creative wisdom and cultural values within OLC community
- provide contribution and enrichment to the OLC Graphic Arts (GART) program and curriculum, and enhance OLC student engagements in Arts & Culture

Awardees will be required to commit 15% of their Residency time to the OLC GART program, through student and community engagement. This may include: critiques, demonstrations, lectures, presentations, workshops, or other GART curriculum development arrangements.

Stipends

Applicants can apply for:

- **80 hours** (max) with 12 hr. contribution to OLC GART = **\$2,400** stipend
- **40 hours** with 6 hr. contribution to OLC GART = **\$1,200** stipend
- **20 hours** (min) with 3 hr. contribution to OLC GART = **\$600** stipend

COVID-19 Precautions

The SPRING 2021 OÁYE - Residency will be conducted entirely ONLINE in conjunction with OLC distance learning and safety procedures. Online requirements are further clarified on page 3*. If an applicant is uncomfortable working with digital platforms, such as Zoom, we encourage you to consider our next application session (Fall 2021), when we anticipate a return to face-to-face class settings. Computer technology is required for SPRING 2021.

The OÁYE program is a partnership between the Graphic Arts program and the Humanities and Social Science department at Oglala Lakota College.

Eligibility

The OÁYE - Residency is open to Master Artists and Cultural Bearers living in the vicinity of the Pine Ridge Indian Reservation, SD. Preference will be given to Oglala Lakota artists but any Master Artist or Cultural Bearer is encouraged to apply. All applications will be reviewed in relevance to Native American Arts & Cultures. **Master Artist** and **Cultural Bearer** is considered anyone with a

substantial amount of demonstrated experience in their field, which may include contemporary, traditional, and cultural art forms.

This program is not limited to the Visual Arts.

Applicant Information

Name:	
Address:	
Phone:	
Email:	
Website/Social Media:	
Tribal Affiliation:	

Online Requirements for Virtual “OÁYE - Residency”

Do you have internet access? (Yes or No, how reliable?)	
Do you have a computer with a webcam and microphone? (Yes or No, unsure?)	
Are you comfortable using “Zoom” (video conference) or other digital formats to document and share your work? (Yes or No, what experience do you have with virtual/online platforms?)	

The OÁYE - Residency cycle for Spring 2021 will be conducted entirely **ONLINE, in conjunction with OLC distance learning and safety procedures. Applicants will need basic experience in and access to online technologies including: internet, computer with webcam/microphone, and digital platforms (Zoom, etc.). OLC GART Faculty will work with applicants to coordinate and manage online engagements.*

Residency requested:

Please indicate which Residency you wish to apply for by checking the box.

- 80 hours** (max) with 12 hr. contribution to OLC GART = **\$2,400** stipend
- 40 hours** with 6 hr. contribution to OLC GART = **\$1,200** stipend
- 20 hours** (min) with 3 hr. contribution to OLC GART = **\$600** stipend

*Total amount of approved program hours to be completed before semester's end.

An equal rate for Materials Support will be added to all approved stipends. Amount to be informed at time of award.

Required Application Materials

Application Checklist

- Residency Proposal** (see prompt below) [file types: word, pdf]
- Resume or CV** [file types: word, pdf, jpeg]
- Portfolio or Work Samples** (10 images) [file types: jpeg, tiff, pdf, mov]
- Artist Statement** (Please tell us what Arts and Culture mean to you; and/or the intention of your work). [file types: word, pdf]
- Headshot** (a picture of yourself to be used for publicity purposes) [file types: jpeg, tiff]
- Supplemental Materials (optional):** articles, reviews, publicity, other

Residency Proposal

[500 word limit]

Please tell us how you intend to use your OÁYE - Residency (projects, goals, timelines).

You may respond to the following prompts:

- Plan of focus during your residency. What do you wish to accomplish?
- Creative and/or cultural goals during your residency.
- Proposed schedule. Indicate residency duration you are applying for and why.
- Creative and/or cultural enrichment. How will your residency support the Oglala Lakota Arts Community, and the OLC GART Program and its student body?
- Resource and Support. How can OLC and the OLC GART program be a resource to you during your residency?

Submit application and all materials to: oaye@olc.edu

Applications will be reviewed by the OÁYE selection committee. All applicants will be notified about their application by email.

For further information or assistance, please contact:

Keith BraveHeart (*OLC GART Faculty*): kbraveheart@olc.edu

Marty Two Bulls Jr. (*OLC GART Faculty*): mtwobullsjr@olc.edu

Kim Bettelyoun (*OLC Humanities and Social Science Department Chair*): kim@olc.edu

OÁYE is an Oglala Lakota Arts Continuum that provides Arts & Culture programming under the Graphic Arts program (GART) at Oglala Lakota College. This initiative is made possible through generous support from the American Indian College Fund for Native Arts Curriculum Development and Enhancement.